

Form PTO 1449 (Modified)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY DOCKET NO. 278727US2PCT		SERIAL NO. 10/550,413	
LIST OF REFERENCES CITED BY APPLICANT				APPLICANT Toshihisa TOMIE			
				FILING DATE September 23, 2005		GROUP 2881	
<b>U.S. PATENT DOCUMENTS</b>							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
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<b>FOREIGN PATENT DOCUMENTS</b>							
		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES NO		
/M.S./	AO	2000-215998	08/04/00	JP (with English abstract & Computer generated translation)		NO	
/M.S./	AP	2000-91095	03/31/00	JP (with English abstract & Computer generated translation)		NO	
/M.S./	AQ	11-250842	09/17/99	JP (with English abstract & Computer generated translation)		NO	
	AR						
<b>OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)</b>							
/M.S./	AS	SUGAR, Jack: "Potential-Barrier Effects in Photoabsorption. II. Interpretation of Photoabsorption Resonances in Lanthanide Metals at the 4d-Electron Threshold", Physical Review B, Vol. 5, No. 5, Pages 1785 -1792, 1972					
/M.S./	AT	O'SULLIVAN, G. et al.: "4d-4f emission resonances in laser-produced plasmas", Journal of Optical Society of America, Vol. 71, No. 3, Pages 227 - 230, 1981.					
/M.S./	AU	BENDER, H.A. et al.: "Velocity characterization of particulate debris from laser-produced plasmas used for extreme-ultraviolet lithography", Applied Optics, Vol. 34, No. 28, Pages 6513 - 6521, 1995.					
/M.S./	AV	"Theoretical consideration on power limit of EUV source", National Institute of Advanced Industrial Science and Technology, AIST01-A00007, Ver. 1.1. Pages 1 - 30, 2002. (with partial English translation)					
/M.S./	AW	SCHWENN, U. et al.: "A Continuous droplet source for plasma production with pulse laser", Journal of Physics E: Scientific Instruments, Vol. 7, Page 715 - 718, 1974.					
/M.S./	AX	RYMELL, L. et al.: "Droplet target for low-debris laser-plasma soft X-ray generation", Optics Communications, Vol. 103, No. 1 - 2, Pages 105 - 110, 1993.					
/M.S./	AY	EICKMANS, Johannes H. et al.: "Plasma spectroscopy H, Li, and Na in plumes resulting from laser-induced droplet explosion", Applied Optics, Vol. 26, No. 17, Pages 3721 - 3725, 1987					
/M.S./	AZ	TOMPKINS, R.J. et al.: "5-20 keV laser-induced x-ray generation at 1 kHz from a liquid-jet target", Review of Scientific Instruments, Vol. 69, No. 9, Pages 3113 - 3117, 1998.				<input type="checkbox"/> Additional References sheet(s) attached	
Examiner /Meenakshi Sahu/							
						Date Considered 01/17/2008	
*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							

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## LIST OF REFERENCES CITED BY APPLICANT

APPLICANT  
Toshihisa TOMIEFILING DATE  
September 23, 2005GROUP  
2881

## U.S. PATENT DOCUMENTS

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	AA						
	AB						
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## FOREIGN PATENT DOCUMENTS

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					YES	NO
/M.S./	AO	2002/46839	06/13/02	WO		NO
/M.S.	AP	2000-215998	08/04/00	JP		NO
/M.S./	AQ	2000-91095	03/31/00	JP		NO
	AR					
	AS					
	AT					
	AU					
	AV					

## OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)

	AW	
	AX	
	AY	
	AZ	

☐ Additional References sheet(s) attached

Examiner /Meenakshi Sahu/

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